

# Spin Hall magneto resistance in epitaxial Ta thin films

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## 1. Introduction

Spin Hall magneto resistance (SMR)[1,2] is one of the effective ways to evaluate the spin Hall angle (SHA) in nonmagnetic materials. Here, we report enhancement of SMR in an epitaxial Ta/CoFeB system and the observed enhancement suggests contributions from bulk and interface to spin Hall effect.

## 2. Experimental procedure

We made the following two different layer structures by radio frequency magnetron sputtering: (A) Al<sub>2</sub>O<sub>3</sub> (0001) substrate / epitaxial  $\alpha$ -Ta ( $d$  nm) / CoFeB(1 nm) / AlO(2 nm) and (B) Si substrate / SiOx / amorphous Ta ( $d$  nm) / CoFeB (1 nm) / AlO (2 nm). The crystal structures of Ta under layers were confirmed by X-ray diffraction and *in-situ* reflection high energy electron diffraction methods. Magneto resistance measurement was performed at room temperature.

## 3. Results

According to the experimental result shown on Fig.1, the enhancement of SMR amplitude, which directly reflects the information of SHA, is a strong evidence that the epitaxial Ta has larger SHA than that in the amorphous Ta below  $d = 3$  nm. The SHA was extracted by fitting theoretical formula to the experimental results [2], and the obtained SHA for both epitaxial and amorphous Ta were 0.13 and 0.08, respectively. Since sheet conductance for epitaxial and amorphous Ta in  $d < 3$  nm show similar values obtained from Fig.2 (92.8  $\mu\Omega\text{cm}$  for epi-Ta, and 95.1  $\mu\Omega\text{cm}$  for amo-Ta), we cannot explain the enhanced SMR amplitude in terms of the intrinsic and/or side jump contributions. The possible origin of this enhancement of SHA in epitaxial Ta might be due to the interface contribution to spin Hall effect.

- [1] H. Nakayama, *et al.*, Phys. Rev. Lett. **110**, 206601 (2013).  
 [2] J. Kim *et al.*, Phys. Rev. Lett. **116**, 097201(2016).

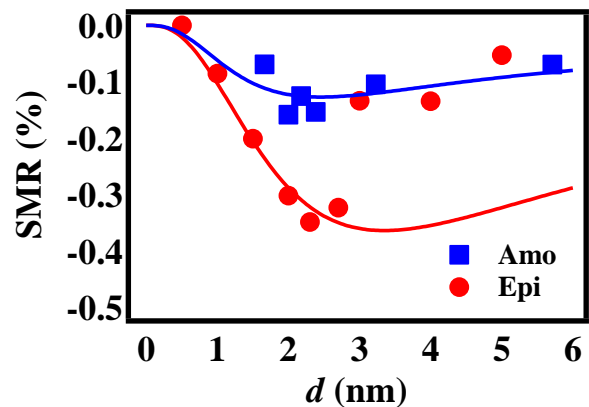


Fig. 1, Ta layer thickness dependence of SMR ratio for both epi-Ta (Red) and amo-Ta (blue). Solid lines indicate theoretical formula.

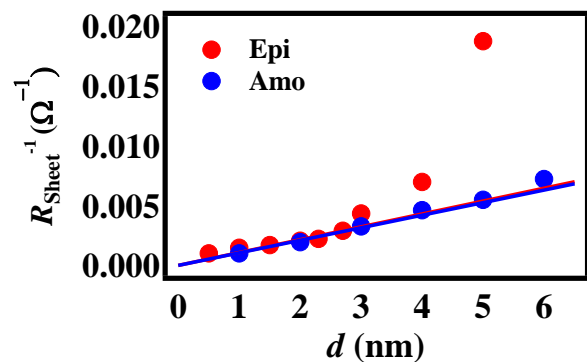


Fig. 2, Ta layer thickness dependence of the sheet conductance for both epi-Ta (Red) and amo-Ta (blue). Solid lines represent the linear fitting to the experimental data in order to estimate the resistivity of the Ta layers. In case of epi-Ta, it was limited the fitting range to  $d < 3$  nm.